# Atomic Layer Deposition (ALD) Coating for Permeation Half-Life Control of Ablator Capsules

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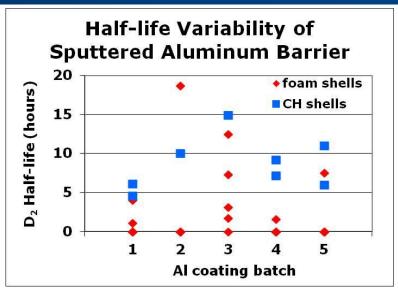


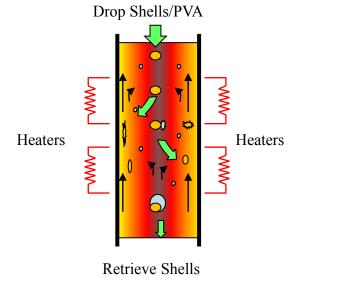
# Atomic Layer Deposition (ALD) shows promise as permeation barrier alternative

- Need to add permeation barrier to target shells to confine fusion fuel from fill until shot
  - GDP target shells leak too fast, ~5 minute D<sub>2</sub> half-life
- Desire ~4-10 hour D<sub>2</sub> half-life
  - Long enough to retain fuel until shell is shot, but short enough to fill by permeation
- Aluminum and PVA have previously been used as permeation barriers
  - Sputtered Al large variation in measured half-life
  - PVA Drop Tower only 5% yield, <900µm OD shells</li>
- Initial ALD results
  - High yield, high throughput, more repeatable
  - Successfully demonstrated with all size shells, various materials, manufactured defects, 3-D features

# Previous methods use aluminum and PVA as permeation barriers, but are far from ideal

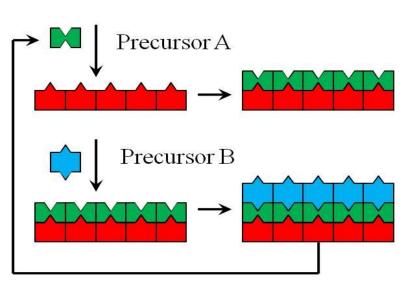
- Sputter aluminum on shells mounted on post or sitting on Gelpak
  - Little control over H-L, due to pinholes/voids in metal coating
  - Unreliable with very large spread even within same batch
  - Opaque layer limits characterization of interior
- Drop shells covered in liquid PVA down tower with heated walls to solidify layer
  - Low yield ~5%
  - Thick and non-uniform  $(3\pm 1 \mu m)$
  - Small shells only (OD <900µm)</li>





# New Method: Atomic Layer Deposition (ALD) provides uniform, pinhole-free very thin coatings





Uniform Al<sub>2</sub>O<sub>3</sub>
Coated on Si Wafer

Grow one monolayer per cycle, ~0.1 nm

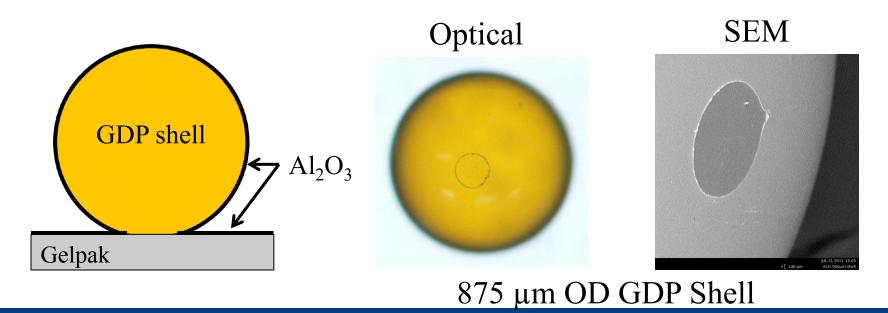
- Designed for thin films, typically <100 nm</li>
- Precursor gas bonds to surface only
- Conforms to structures, high aspect ratios

### Transparent Al<sub>2</sub>O<sub>3</sub> process very robust

- Low coating temperature is ideal for plastics
- Process does not damage shell

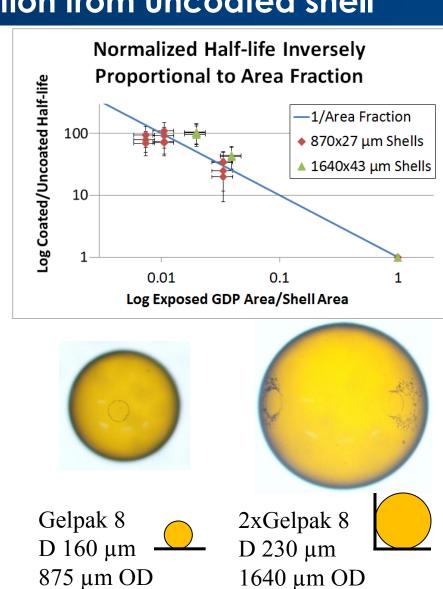
# Shells are placed on Gelpak<sup>®</sup> in ALD chamber, leaving the contact spot uncoated

- Conformal coating everywhere except where shell is in contact with Gelpak
  - Contact spot area determined by Gelpak retention level (0,4,8), shell size, and shell weight
- Using Gelpak 8 leaves potentially undesirable Gelpak still attached to shell in visible residue ring



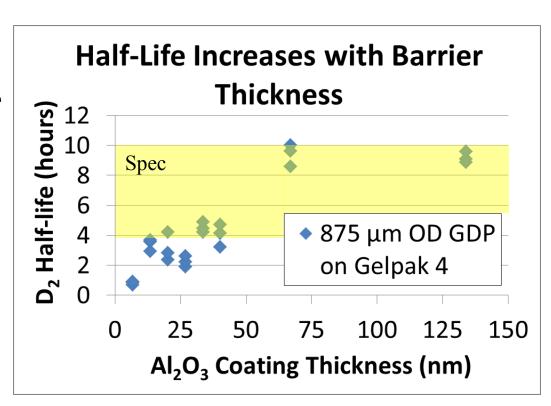
## Method 1: Deliberately use area of exposed GDP at contact spot to scale permeation from uncoated shell

- Permeation rate of D<sub>2</sub> through the Al<sub>2</sub>O<sub>3</sub> layer << GDP shell wall</li>
  - Thickness of Al<sub>2</sub>O<sub>3</sub>~35 nm
- Assume all gas permeates through exposed GDP at contact spot, then expect Halflife (inverse of permeation rate) to scale with inverse of exposed GDP area
  - Area defined by residue ring
- Higher order corrections to model
  - Exposed GDP area different from residue ring
  - Al<sub>2</sub>O<sub>3</sub> layer semi-permeable



# Method 2: Using a fixed contact area, vary the thickness to change the permeation rate

- Large range of thicknesses produce desired barrier
- More repeatable and fine control compared to sputtered Al
- 10 hour half-life max due to permeation through contact spot
  - Up to 50 hour half-lives achieved by flipping shell during coating, sealing contact spots

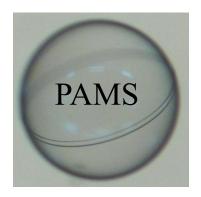


By varying exposed GDP area and Al<sub>2</sub>O<sub>3</sub> thickness, we can achieve greater flexibility and control over barrier

# Conformal ALD coatings are ideal for use on complex geometries and 3-D features

- Transparent ALD coating conforms to surface, preserving features
- Example: successfully coated 8 µm deep x 30 µm wide trench
  - 25 nm flipped coating (2x12.5 nm) resulted in 32 hr half-life w/ trench, 40 hr w/o
  - Sputtered permeation barrier was unsuccessful due to shadowing and other non-uniformities
- Can be extended to other 3-D features and targets (not just shells)
  - Up to 5000:1 aspect ratios in literature





875 μm OD 17 μm wall

#### ALD coatings have other attractive benefits

- Able to coat on variety of materials
  - Plastic, silicon, oxides, metals, carbon
- Thin ALD coatings are amorphous, stronger and harder compared to bulk materials
- Al<sub>2</sub>O<sub>3</sub> process is temperature independent
  - Demonstrated 120 °C, 80 °C, literature down to room temp
  - Ideal for temp sensitive plastics
- Other materials available
  - Oxides (including conductive), nitrides, metals
  - Adaptable to include other materials

# Future research aims to dial in desired half-life and for shells to be used in real shot experiment

- Acquire more data and statistics to further validate permeation barrier model
- Experiment with other ways of selecting exposed area/masking
- Investigate and eliminate residual ring when shell removed from Gelpak
- Study initial seeding behavior of Al<sub>2</sub>O<sub>3</sub>
  using Quartz Crystal Microbalance
  (QCM) to further increase repeatability
  and understanding

